

A Large-Signal Physical MESFET Model for Computer-Aided Design and Its Applications

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Abstract—A quasi-static, large-signal MESFET circuit model has been developed. It is based on a comprehensive quasi-two-dimensional semiclassical device physical simulation where its unique formulation and efficiency make it suitable for the computer-aided design of nonlinear MESFET subsystems. Using this approach the semiconductor equations are reduced to a consistent one-dimensional approximation requiring substantially less computing resources than a full two-dimensional simulation. CPU time is typically reduced by a factor of 1000. A single/two-tone harmonic balance analysis procedure which employs the describing frequency concept has also been developed and combined with the MESFET model. Numerical load-pull contours, as well as intermodulation distortion contours, have been simulated and comparison of these with measured results validates the approach taken.

I. INTRODUCTION

GaAs MESFET's are the fundamental building block for both discrete and monolithic microwave integrated circuits (MMIC's). The requirements to minimize development costs and optimize device-circuit interaction have led to an increased interest in physical device models which intrinsically relate the basic material and geometrical parameters of a device to its dc and RF performance. Moreover, the trend toward higher frequency of operation (shorter gate length devices) requires models capable of describing non-equilibrium transport phenomena (hot-electron effects). Many two-dimensional physical simulations which provide insight into the device operation have been proposed [1]–[5], but these require large computing resources and are not, as yet, generally applicable in the design process. The model presented here is based on a description of the carrier dynamics (transport equations) derived from the Boltzmann equation [6].

The validity of the model for both dc and small-signal (S -parameter) conditions has been assessed previously [7], [8] and the object of this paper is the application of the model to the computer-aided design (CAD) of nonlinear microwave subsystems when device-circuit interaction can be addressed and sensitivity analysis performed as a function of the basic device parameters. To this end a quasi-

static, large-signal MESFET model has been derived from the simulation and combined with an efficient single/two-tone harmonic balance analysis procedure in order to simulate load-pull and intermodulation distortion contours.

The basis of the quasi-two-dimensional physical simulation is described in Section II and the quasi-static, large-signal MESFET circuit model is presented in Section III together with simulated results for a power device used throughout the work. Section IV describes the single/two-tone nonlinear analysis procedure developed and this is followed by experimental results, in Section V.

II. QUASI-TWO-DIMENSIONAL PHYSICAL MESFET SIMULATION

A. Transport Equations

The physical simulation is based on the four semiclassical semiconductor equations coupled with analytical expressions for the MESFET channel. The model accounts for process-related parameters (geometry, recess depth, material parameters, doping profile, etc.), surface depletion effects, substrate conduction, contact resistivities, avalanche breakdown, and forward gate conduction [8]. A more complete carrier transport model than in previous quasi-two-dimensional simulations [9], [10] is employed and the Poisson and current continuity equations are solved together with the energy and momentum conservation equations. The solution of the latter allows hot-electron effects (velocity overshoot) to be simulated, thus making the model also suitable for short-gate-length MESFET's.

The basic simplifying assumptions for the MESFET channel, based on the results of full two-dimensional simulations, are

- i) no current flows through the depleted region,
- ii) current density is one-dimensional,
- iii) potential contours in the undepleted part of the active channel and in the substrate are all parallel and are perpendicular to the active layer/substrate interface.

Fig. 1 shows the model geometry which derives from these. Approximation iii) provides continuity of potential,

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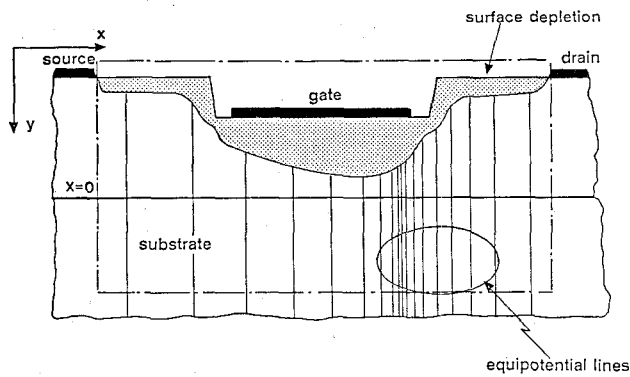


Fig. 1. Model geometry for the quasi-two-dimensional model.

with charge being continuous across the interface, leading to a substrate charge n_s and consequently a substrate current. This is represented in the model by an equivalent channel thickness to account for electrons being injected into the substrate [8].

For this quasi-two-dimensional model, the two-dimensional semiconductor equations are reduced to a one-dimensional set consistent with the approximations described, taking the forms given below.

Poisson's equation is

$$\frac{\partial E_x y}{\partial x} = \frac{q}{\epsilon_r} (N_D - n) y \quad (1)$$

where E_x is the longitudinal component of the electric field, y is the equivalent conductive channel height, N_D is the doping level, and n is the electron density. Equation (1) is obtained by applying Gauss' law to an incremental volume element. It assumes that the electric field flux across the gate depletion region is zero and that the electric field has no transversal component in the substrate.

The equation for current continuity is

$$\frac{\partial nyv}{\partial x} + \frac{\partial ny}{\partial t} = 0 \quad (2)$$

where v is the electron velocity (assumed one-dimensional). Following Cook and Frey's work [3], the equations for momentum and energy conservation are described by

$$v = \mu \left[E_x - \frac{2}{3} K \frac{\partial W}{\partial x} - \frac{2}{3} (W - G_U \Delta_{LU}) \frac{1}{n} \frac{\partial n}{\partial x} \right] \quad (3)$$

$$\frac{\partial W}{\partial x} = \frac{1}{1 + \frac{2}{3} K} \left[E_x - \frac{W - W_0}{v \tau_w} \right] \quad (4)$$

where μ is the electron mobility, τ_w the energy relaxation time (both functions of the average electron energy W), and W_0 is the lattice energy. G_U (the upper valley fraction) and K ($K = \partial G_U / \partial W$) account for the two-valley nature of GaAs and Δ_{LU} is the lower to upper valley energy gap (0.36 eV for GaAs). Equation (3) shows the electron velocity in its drift and diffusion form. The last term in (3) can be neglected, however, since it has been shown that longitudinal thermal diffusion is dominant in the hot electron range [3]. The energy conservation equation (4) states that

the electron energy flow balances the energy loss due to collisions together with the energy gain by Joule heating due to the electric field. In equations (3) and (4) energy-dependent material parameters are obtained by curve fitting the results of Monte Carlo simulations [9].

B. MESFET Simulation

Using the finite difference technique, the MESFET channel is divided into incremental sections of length Δx , and a backward difference scheme, which follows the carrier displacement from source to drain, is applied. The required boundary conditions are the gate voltage and the source current. The discretized form of (1) to (4) (no time dependence in (2)) is combined with analytical expressions for both the gate and the surface depletion depth resulting in a quadratic equation for the electron velocity at each mesh point in the MESFET channel. The coefficients in this equation are all functions of the average electron energy, so that an iterative procedure is necessary. Generally not more than five iterations are required to guarantee satisfactory convergence. The main consequence of this efficiency is that the typical CPU time for a full channel simulation is of the order of 0.6 s on a VAX 8600, representing a reduction by a factor of approximately 1000 compared to a full two-dimensional simulation. Typical simulated results for the device used in this work can be found elsewhere [8].

III. QUASI-STATIC LARGE-SIGNAL MESFET EQUIVALENT CIRCUIT MODEL

The drive toward large-scale integration, often using monolithic techniques, requires efficient CAD tools capable of predicting and optimizing device and circuit large-signal performance prior to fabrication.

An approach whereby a quasi-static, large-signal MESFET equivalent circuit model is derived from a numerical simulation has been developed. From Poisson's and current continuity equations one can identify the basic phenomena that need to be accounted for when developing a MESFET circuit model. Substitution of (1) in (2) provides

$$\frac{\partial qnyv}{\partial x} - \epsilon_r \frac{\partial}{\partial t} \left[\frac{\partial E_x y}{\partial x} \right] + q \frac{\partial N_D y}{\partial t} = 0. \quad (5)$$

Equation (5) shows that at every point in the channel the current is formed by a conduction component and a displacement counterpart. The latter is caused by the capacitive nature of both the domain created in the device channel (second term in (5)) and the expansion of the gate depletion region (third term). Under the quasi-static assumption the conduction and displacement currents give rise to lumped nonlinear current sources and capacitors, respectively.

For each simulated point of the device characteristics (I_{DS} versus V_{DS}), small perturbations of the gate voltage and/or source current (the independent variables for the physical simulation) provide the MESFET's equivalent circuit element values G_m , G_{DS} (represented by I_{DS}), C_{GS} , C_{DG} , and C_{DOM} , shown in Fig. 2 The voltage and charge

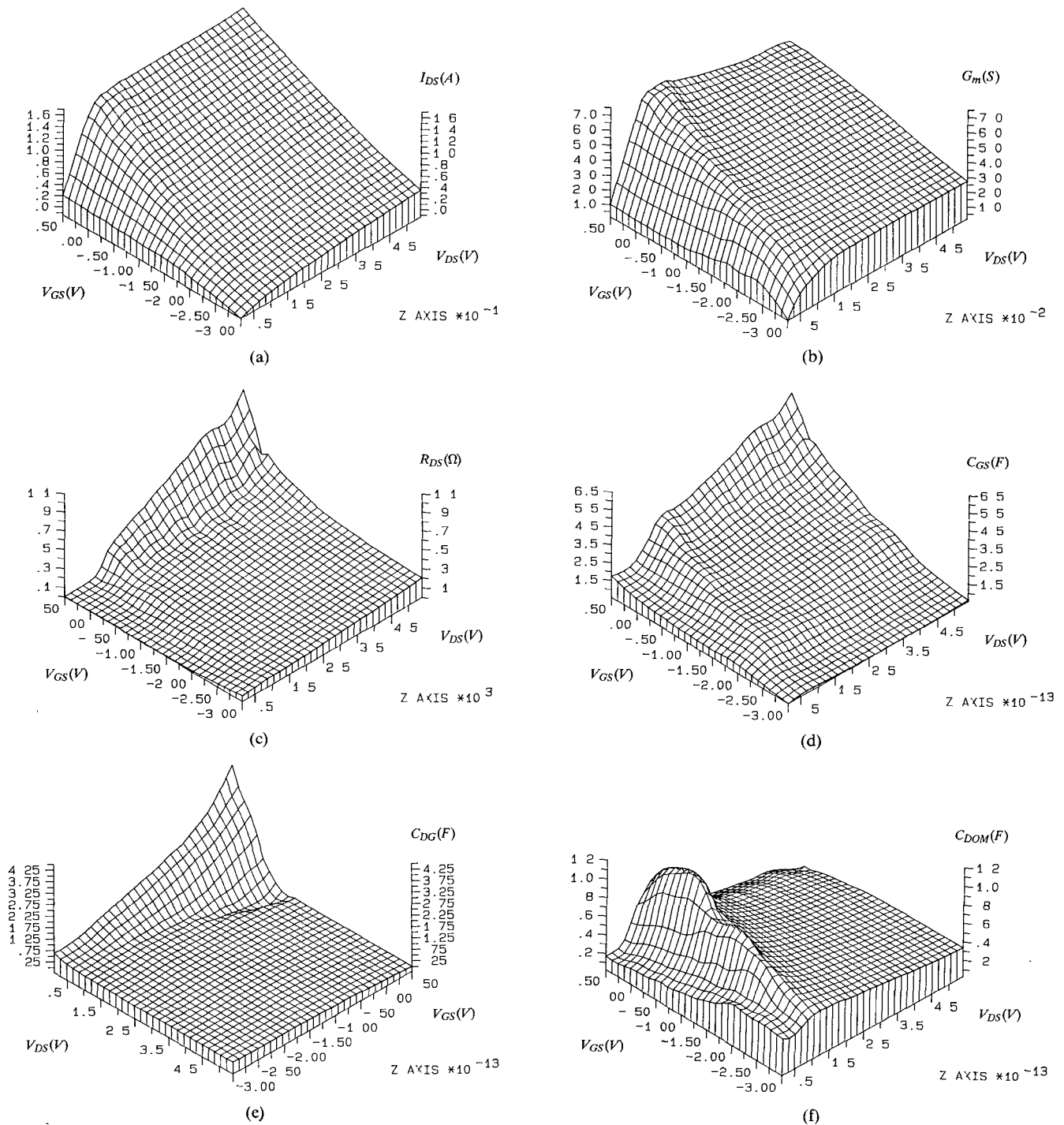


Fig. 3. NE9000 equivalent circuit element values. (a) I_{DS} , (b) G_m , (c) R_{DS} , (d) C_{GS} , (e) C_{DG} , and (f) C_{DOM} . Bias range is $V_{GS} = -3.0$ to $+0.5$ V and $V_{DS} = 0$ to 5.0 V.

where load-pull contours of gain (Fig. 5(a)) and output power (Fig. 5(b)) corresponding to the 1 dB compression point are shown.

Fig. 6 shows the simulated results of the two-tone procedure with signals at 9.99 and 10.00 GHz with equal input powers (again for 1 dB compression). It can be seen that both the gain and output power contours are similar in shape to those in Fig. 5, but an output power compression effect can be clearly seen whereby for the same values of

gain at the 1 dB compression point in both the single- and two-tone situations (Figs. 5(a) and 6(a)), the corresponding output powers differ by 5 dB (Figs. 5(b) and 6(b)). Fig. 6(c) and (d) shows intermodulation distortion contours for both a low drive level (10 dB below 1 dB compression) and for the 1 dB compression point. It is evident that there is a tendency for the optimum load termination for minimum IMD to move toward the center of the chart as the power is increased.

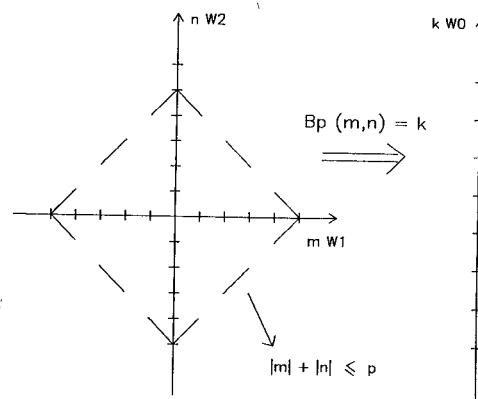


Fig. 4. Bilinear transformation of the two-dimensional frequency grid onto an equivalent one-dimensional spectrum.

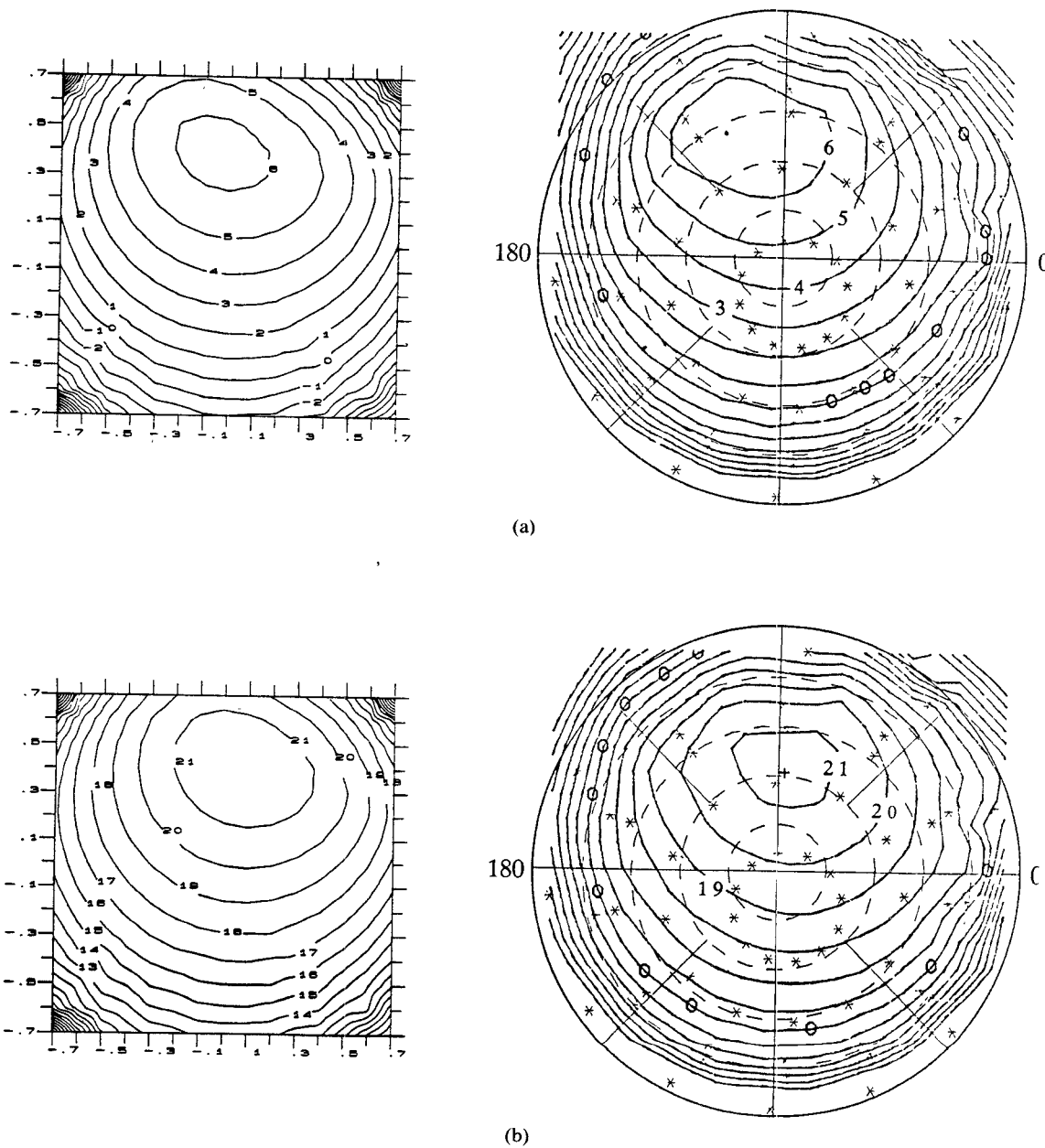


Fig. 5. Measured and simulated load-pull contours of (a) gain and (b) output power at the 1 dB compression point.

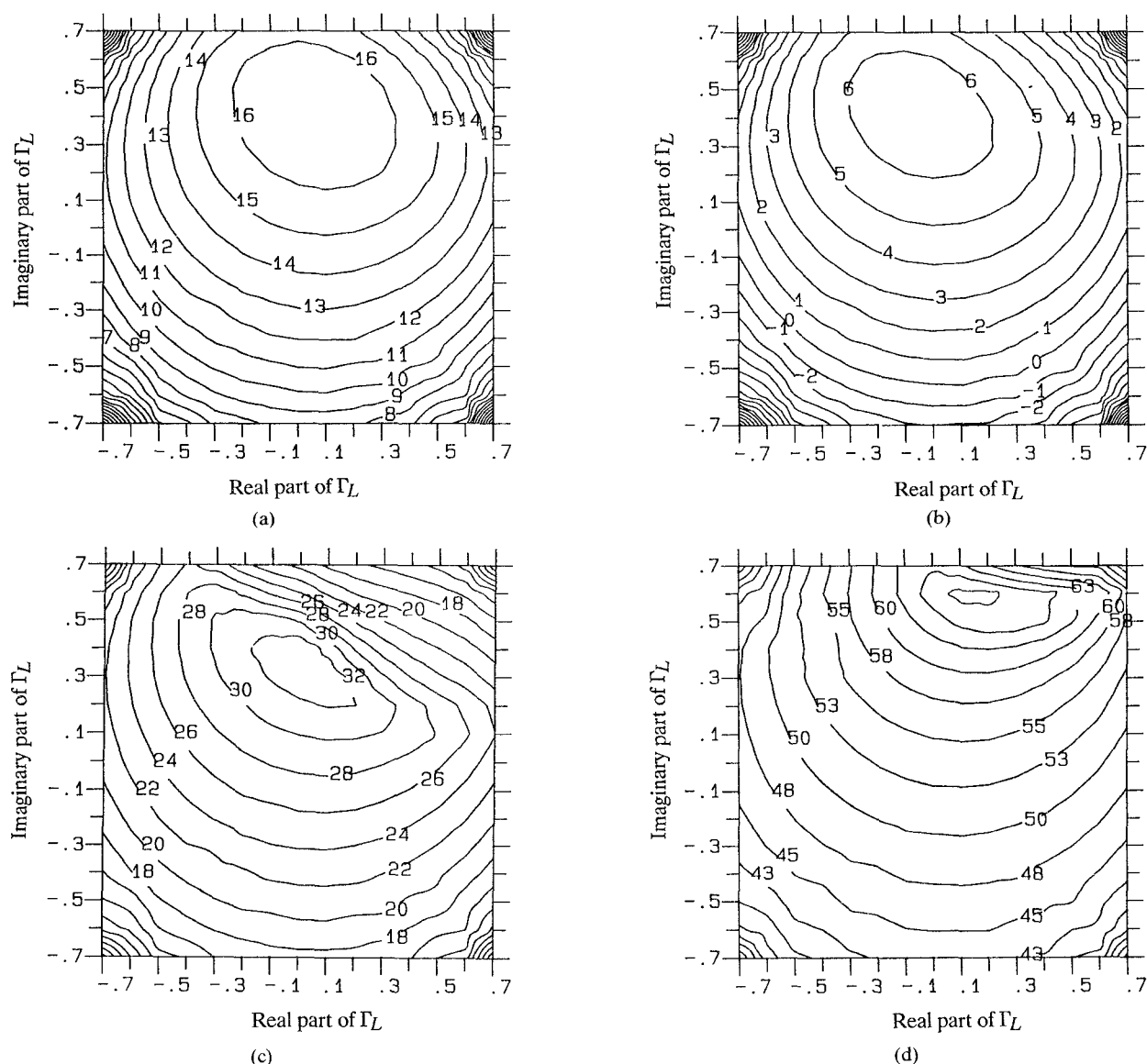


Fig. 6. Simulated two-tone harmonic balance load-pull contours of (a) gain, (b) output power at the 1 dB compression point, (c) IMD at the 1 dB compression point, and (d) IMD contours at 10 dB below the 1 dB compression point.

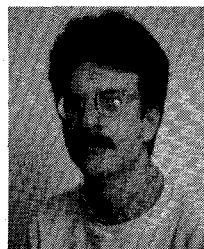
VI. CONCLUSIONS

A quasi-static, large-signal MESFET model based on a quasi-two-dimensional device physical simulation has been developed and combined with a single/two-tone harmonic balance analysis procedure. Application of the describing frequency concept drastically reduced the complexity of the two-tone excitation problem by transforming it to an equivalent single-tone case. Numerical load-pull contours, as well as intermodulation distortion contours, have been simulated and excellent agreement with experimental results has been demonstrated.

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